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AF

THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of : **Confirmation No. 1092**  
Hiroto YUKAWA et al. : Attorney Docket No. 2004\_0499  
Serial No. 10/810,902 : Group Art Unit 1752  
Filed March 29, 2004 : Examiner Sin J. Lee  
  
POSITIVE-WORKING CHEMICAL-  
AMPLIFICATION PHOTORESIST  
COMPOSITION : **Mail Stop: AF**

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**RESPONSE TO FINAL REJECTION**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In Response to the Final Rejection dated July 12, 2006, please amend the present application as follows: